

#### **Feature**

- Precision MEMS process
- High performance, shielded, Micro-cavity structure
- Silicon substrate, 50Ω CPW output
- Au wire bonding, for MCM applications

## **Environmental Specifications**

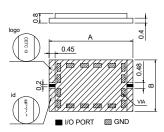
Operating Temperature	-55℃~+85℃	
Storage Temperature	-55°C∼+125°C	
Max. Input Power	35dBm	

# Electrical Specifications(T<sub>A</sub>=+25°C)

Parameter	Min.	Тур.	Max.	Unit
Center Freq. (f₀)	-	10.8	-	GHz
Pass Band	10.1	-	11.5	GHz
Ripple in Pass band	-	-	1	dB
Insertion Loss @ f₀	-	-	2.5	dB
Return Loss	12	-	-	dB
	≥30@9.5GHz&12.1GHz			dB
Out of band	≥40@9.3	dB		
Attenuation	≥60@DC~8.5GHz			dB
	≥50@13~24GHz			dB
Group Delay Variation	≤1@10.1~11.5GHz			
Linear Phase	≤±7@10	0		

S2P file name: SiMF10R72\_1R16-8D3.s2p

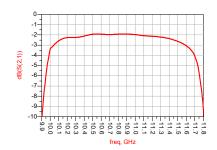
## **Outline Drawing**



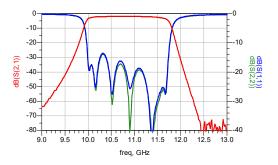
Symbol	Value (mm)			
Symbol	Min.	Nominal	Max.	
А	7.9	-	8.0	
В	3.9	-	4.0	

## **Typical Test Curves**

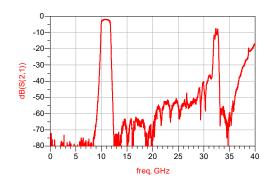
Insertion Loss VS Frequency (T<sub>A</sub>=25°C)



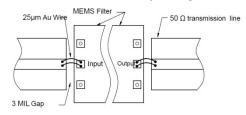
Insertion Loss & Return Loss VS Frequency (T<sub>A</sub>=25°C)



Broadband Insertion Loss VS Frequency (T<sub>A</sub>=25°C)

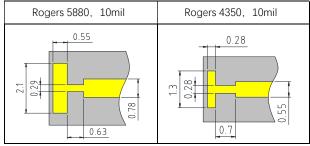


#### **Recommended Assembly Diagrams**



### **Application Notes:**

- 1. The chip is back-metalized and can be die mounted with AuSn eutectic performs or with electrically conductive epoxy (for example ME8456).
- 2. The die should be assembled on carriers like Kovar or Mu-Cu which have same Coefficient of thermal expansion. (2.9ppm/ $^{\circ}$ C) with Silicon, thickness 0.2mm max.
- 3. Handle the chips in a clean environment. DO NOT attempt to clean the chip using liquid cleaning systems.
- 4. Handle the chip along the edges with a vacuum collet or with a sharp pair of bent tweezers.
- 5. Recommended to use T structure as below for bonding.



6. If you have any questions, please contact us.